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Jiro KONDO, et al.

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FILING DATE GROUP
August 29, 2006 Not Yet Assigned

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EXAMINER /Stefanie Cohen/	DATE CONSIDERED	07/18/2008
EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E. not considered. Include conv. of this form with next communication to applicant	P. 609; draw line through citation if not in	conformance and